



FORM PTO-1449	SERIAL NO. 09/938,056	CASE NO. 7103/205
LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT		FILING DATE August 23, 2001
(use several sheets if necessary)		APPLICANT(S): Youlin J. Li, et al.

REFERENCE DESIGNATION **U.S. PATENT DOCUMENTS**

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS/ SUBCLASS	FILING DATE
GN	A1 5,225,034	07-06-1993	Yu et al.		
	A2 5,340,370	08-23-1994	Cadien et al.		
	A3 5,354,490	10-11-1994	Yu et al.		
	A4 5,516,346	05-14-1996	Cadien et al.		
	A5 5,692,947	12-02-1997	Talieh et al.		
	A6 5,762,536	06-09-1998	Pant et al.		
	A7 5,836,806	11-17-1998	Cadien et al.		
	A8 5,840,629	11-24-1998	Carpio		
	A9 5,863,307	01-26-1999	Zhou et al.		
	A10 5,863,835	01-26-1999	Yoo et al.		
	A11 5,871,390	02-16-1999	Pant et al.		
	A12 5,897,375	04-27-1999	Watts et al.		
	A13 5,954,997	09-21-1999	Kaufman et al.		
	A14 5,985,748	11-16-1999	Watts et al.		
	A15 6,001,730	12-14-1999	Farkas et al.		
	A16 6,010,962	01-04-2000	Liu et al.		
	A17 6,027,997	02-22-2000	Yu et al.		
	A18 6,046,099	04-04-2000	Cadien et al.		
	A19 6,048,796	04-11-2000	Wang et al.		
	A20 6,063,306	05-16-2000	Kaufman et al.		
	A21 6,066,028	05-23-2000	Cheng et al.		
	A22 6,083,840	07-04-2000	Mravic et al.		
	A23 6,096,652	08-01-2000	Watts et al.		
	A24 6,114,246	09-05-2000	Weling		
	A25 6,126,853	10-03-2000	Kaufman et al.		
	A26 6,140,239	10-31-2000	Avanzino et al.		
GN	A27 6,336,845	01-08-2002	Engdahl et al.		

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS/ SUBCLASS	TRANSLATION YES	NO

EXAMINER INITIAL	OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)	
GN	A28	U.S. Patent Application Serial No. 09/540,810, Entitled: "Fixed Abrasive Linear Polishing Belt And System," Inventor: Cangshan Xu, et al. (as filed).

EXAMINER INITIAL	DATE CONSIDERED
	10/31/02

EXAMINER Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.